

IN THE CLAIMS:

Claims 1-160 have been cancelled.

Please add new claims 161-164 as follows:

161 (new) A chemical vapor deposition reactor system comprising:
a plurality of chambers;
a rotatable wafer carrier disposed within each of the chambers; and
a common reactant gas supply configured to provide substantially the same gas mixture to each chamber.

162 (new) The chemical vapor deposition reactor system as recited in claim 161, further comprising a common gas exhaust system for the chambers.

163 (new) The chemical vapor deposition reactor system as recited in claim 161, wherein each chamber is a comparatively small chamber.

164 (new) The chemical vapor deposition reactor system as recited in claim 161, wherein each chamber defines a seven wafer reactor.

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